

L26 ANSWER 39 OF 40 CAPLUS COPYRIGHT 2003 ACS on STN

AN 2002:314503 CAPLUS

DN 136:348304

TI Positive photosensitive composition

IN Kodama, Kunihiko; Aoai, Toshiaki

PA Fuji Photo Film Co., Ltd., Japan

SO Eur. Pat. Appl., 148 pp.

CODEN: EPXXDW

DT Patent

LA English

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 1199603	A1	20020424	EP 2001-124329	20011019
	R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR				
	JP 2002131897	A2	20020509	JP 2000-321128	20001020
	JP 2002214774	A2	20020731	JP 2001-132546	20010427
	US 2002102491	A1	20020801	US 2001-978103	20011017 ✓

PRAI JP 2000-321128 A 20001020  
JP 2000-352899 A 20001120  
JP 2001-132546 A 20010427

AB A pos. photosensitive compn. comprises a compd. capable of generating a specified sulfonic acid upon irradn. with one of an actinic ray and radiation and a resin capable of decompg. under the action of an acid to increase the solv. in an alkali developer.

IT 195000-67-0 216308-45-1 250378-10-0  
258879-87-7 288303-55-9 297156-40-2  
301664-71-1 304441-22-3 324770-96-9  
357413-69-5 398141-19-0 414911-37-8  
414911-60-7 414911-65-2 414911-75-4  
414911-76-5 415920-54-6

RL: TEM (Technical or engineered material use); USES (Uses)  
(photo-acid generator used in pos. photoresist compn.)

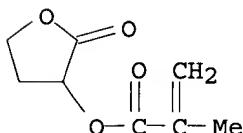
RN 195000-67-0 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-methyltricyclo[3.3.1.13,7]dec-2-yl ester, polymer with tetrahydro-2-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 195000-66-9

CMF C8 H10 O4

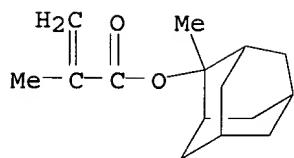


230 - 232

CM 2

CRN 177080-67-0

CMF C15 H22 O2



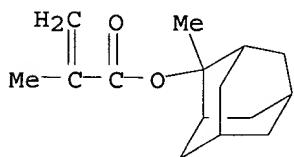
RN 216308-45-1 CAPLUS

CN 2-Propenoic acid, 2-methyl-, polymer with 2-methyltricyclo[3.3.1.1<sup>3,7</sup>]dec-2-yl 2-methyl-2-propenoate and tetrahydro-4-methyl-2-oxo-2H-pyran-4-yl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 177080-67-0

CMF C15 H22 O2



CM 2

CRN 177080-66-9

CMF C10 H14 O4

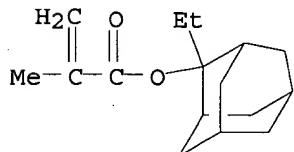
RN 250378-10-0 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-ethyltricyclo[3.3.1.13,7]dec-2-yl ester,  
polymer with tetrahydro-2-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA  
INDEX NAME)

CM 1

CRN 209982-56-9

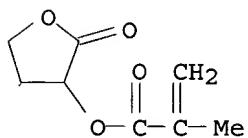
CMF C16 H24 O2



CM 2

CRN 195000-66-9

CMF C8 H10 O4



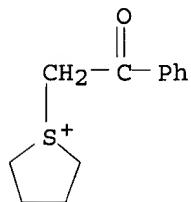
RN 301664-71-1 CAPLUS

CN Thiophenium, tetrahydro-1-(2-oxo-2-phenylethyl)-, salt with  
1,1,2,2,3,3,4,4-nonafluoro-1-butanesulfonic acid (1:1) (9CI) (CA INDEX  
NAME)

CM 1

CRN 58162-29-1

CMF C12 H15 O S



CM 2

CRN 45187-15-3

CMF C4 F9 O3 S

-O<sub>3</sub>S-(CF<sub>2</sub>)<sub>3</sub>-CF<sub>3</sub>

L26 ANSWER 40 OF 40 CAPLUS COPYRIGHT 2003 ACS on STN  
 AN 2002:119352 CAPLUS  
 DN 136:175472  
 TI Positive photosensitive composition for photofabrication using deep UV ray  
 IN Kodama, Kunihiko; Aoai, Toshiaki  
 PA Fuji Photo Film Co., Ltd., Japan  
 SO Eur. Pat. Appl., 120 pp.  
 CODEN: EPXXDW

DT Patent

LA English

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 1179750	A1	20020213	EP 2001-117796	20010802
	R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO				
	JP 2002122994	A2	20020426	JP 2001-188670	20010621
	US 2002051933	A1	20020502	US 2001-921691	20010806
	US 6492091	B2	20021210		
PRAI	JP 2000-240059	A	20000808		

AB A pos. photosensitive compn. comprises: (A) a compd. generating an acid upon irradn. with one of an actinic ray and radiation; (B) a resin contg. a monocyclic or polycyclic alicyclic hydrocarbon structure and increasing the solv. to an alkali developer by the action of an acid; and (C) an onium salt of carboxylic acid. The present invention relates to a pos. photosensitive compn. for use in the prodn. process of a semiconductor such as IC, in the prodn. of a circuit board such as liq. crystal and thermal head, and in other photofabrication processes.

IT 398141-62-3 398141-63-4

RL: TEM (Technical or engineered material use); USES (Uses)  
 (onium salt; deep UV photofabrication pos. photoresist compn.  
 contg.)

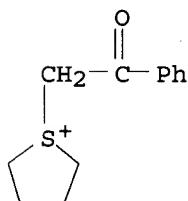
RN 398141-62-3 CAPLUS

CN Thiophenium, tetrahydro-1-(2-oxo-2-phenylethyl)-, methanesulfonate (9CI)  
 (CA INDEX NAME)

CM 1

CRN 58162-29-1

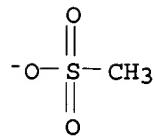
CMF C12 H15 O S

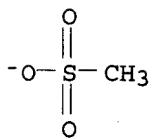


CM 2

CRN 16053-58-0

CMF C H3 O3 S





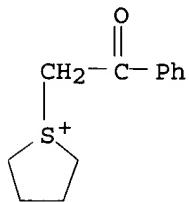
RN 398141-63-4 CAPLUS

CN Cholan-24-oic acid, 3,7,12-trihydroxy-, ion(1-),  
(3.alpha.,5.beta.,7.alpha.,12.alpha.)-, tetrahydro-1-(2-oxo-2-phenylethyl)thiophenium (9CI) (CA INDEX NAME)

CM 1

CRN 58162-29-1

CMF C12 H15 O S

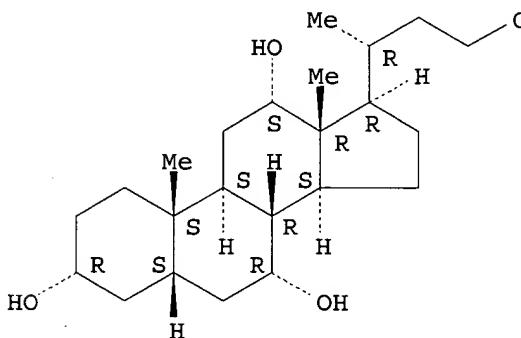


CM 2

CRN 298-43-1

CMF C24 H39 O5

Absolute stereochemistry.



IT 301664-71-1 301664-72-2 398141-19-0

398141-23-6

RL: TEM (Technical or engineered material use); USES (Uses)  
(photoacid generator; deep UV photofabrication pos. photoresist  
compr. contg.)

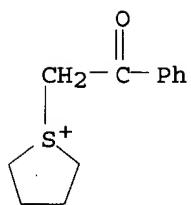
RN 301664-71-1 CAPLUS

CN Thiophenium, tetrahydro-1-(2-oxo-2-phenylethyl)-, salt with  
1,1,2,2,3,3,4,4,4-nonafluoro-1-butanesulfonic acid (1:1) (9CI) (CA INDEX  
NAME)

CM 1

CRN 58162-29-1

CMF C12 H15 O S



CM 2

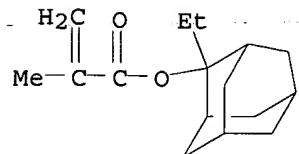
CRN 45187-15-3  
CMF C4 F9 O3 S

-O<sub>3</sub>S-(CF<sub>2</sub>)<sub>3</sub>-CF<sub>3</sub>

RN 301664-72-2 CAPLUS  
CN Thiophenium, tetrahydro-1-(2-oxo-2-phenylethyl)-, salt with  
1,1,2,2,3,3,4,4,5,5,6,6,7,7,8,8,8-heptadecafluoro-1-octanesulfonic acid  
(1:1) (9CI) (CA INDEX NAME)

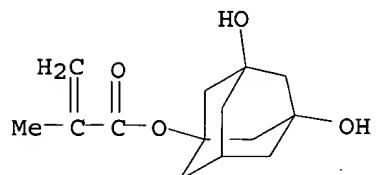
CM 2

CRN 209982-56-9  
CMF C16 H24 O2



CM 3

CRN 115522-15-1  
CMF C14 H20 O4



L29 ANSWER 36 OF 37 CAPLUS COPYRIGHT 2003 ACS on STN

AN 2002:314503 CAPLUS

DN 136:348304

TI Positive photosensitive composition

IN Kodama, Kunihiko; Aoai, Toshiaki

PA Fuji Photo Film Co., Ltd., Japan

SO Eur. Pat. Appl., 148 pp.

CODEN: EPXXDW

DT Patent

LA English

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 1199603	A1	20020424	EP 2001-124329	20011019
	R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR				
	JP 2002131897	A2	20020509	JP 2000-321128	20001020
	JP 2002214774	A2	20020731	JP 2001-132546	20010427
	US 2002102491	A1	20020801	US 2001-978103	20011017

PRAI JP 2000-321128 A 20001020

JP 2000-352899 A 20001120

JP 2001-132546 A 20010427

AB A pos. photosensitive compn. comprises a compd. capable of generating a specified sulfonic acid upon irradn. with one of an actinic ray and radiation and a resin capable of decompg. under the action of an acid to increase the solv. in an alkali developer.

IT 301664-71-1 398141-19-0 414911-37-8

414911-60-7 414911-65-2 414911-75-4

414911-76-5 414911-87-8 414911-88-9

RL: TEM (Technical or engineered material use); USES (Uses)  
(photo-acid generator used in pos. photoresist compn.)

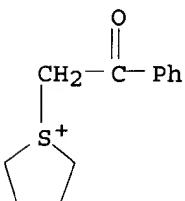
RN 301664-71-1 CAPLUS

CN Thiophenium, tetrahydro-1-(2-oxo-2-phenylethyl)-, salt with  
1,1,2,2,3,3,4,4,4-nonafluoro-1-butanesulfonic acid (1:1) (9CI) (CA INDEX  
NAME)

CM 1

CRN 58162-29-1

CMF C12 H15 O S



CM 2

CRN 45187-15-3

CMF C4 F9 O3 S

-O3S-(CF2)3-CF3

RN 398141-19-0 CAPLUS

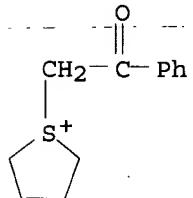
CN Thiophenium, tetrahydro-1-(2-oxo-2-phenylethyl)-, salt with

trifluoromethanesulfonic acid (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 58162-29-1

CMF C12 H15 O S



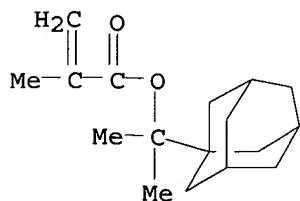
RN 414911-87-8 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 1-methyl-1-tricyclo[3.3.1.13,7]dec-1-ylethyl ester, polymer with 3-hydroxytricyclo[3.3.1.13,7]dec-1-yl 2-propenoate and tetrahydro-2-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 279218-76-7

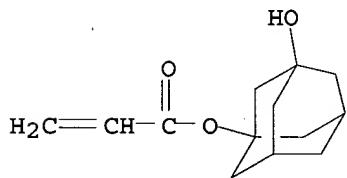
CMF C17 H26 O2



CM 2

CRN 216581-76-9

CMF C13 H18 O3



CM 3

CRN 195000-66-9

CMF C8 H10 O4

(FILE 'HOME' ENTERED AT 16:30:39 ON 20 AUG 2003)

FILE 'REGISTRY' ENTERED AT 16:30:57 ON 20 AUG 2003

L1 SCREEN 970 AND 2067  
L2 STRUCTURE UPLOADED  
L3 QUE L2 AND L1  
L4 SCREEN 970 AND 2067  
L5 STRUCTURE UPLOADED  
L6 QUE L5 AND L4  
L7 SCREEN 970 AND 2067  
L8 STRUCTURE UPLOADED  
L9 QUE L8 AND L7  
L10 SCREEN 963 AND 970 AND 1006 AND 2067  
L11 STRUCTURE UPLOADED  
L12 QUE L11 AND L10  
L13 SCREEN 970 AND 2067  
L14 STRUCTURE UPLOADED  
L15 QUE L14 AND L13  
L16 SCREEN 970 AND 2067  
L17 STRUCTURE UPLOADED  
L18 QUE L17 AND L16  
L19 922 S L3 FULL

FILE 'CAPLUS' ENTERED AT 16:33:56 ON 20 AUG 2003

L20 452 S L19  
L21 32183 S PHOTORESIST OR RESIST COMPOSITION  
L22 391 S L20 AND L21

FILE 'REGISTRY' ENTERED AT 16:36:46 ON 20 AUG 2003

L23 STRUCTURE UPLOADED  
L24 130 S L23 FULL

FILE 'CAPLUS' ENTERED AT 16:37:07 ON 20 AUG 2003

L25 127 S L24  
L26 40 S L22 AND L25

FILE 'REGISTRY' ENTERED AT 16:46:33 ON 20 AUG 2003

L27 439 S L18 FULL

FILE 'CAPLUS' ENTERED AT 16:47:03 ON 20 AUG 2003

L28 139 S L27  
L29 37 S L21 AND L28 AND L25

FILE 'REGISTRY' ENTERED AT 16:53:14 ON 20 AUG 2003

=> s l15 full  
FULL SEARCH INITIATED 16:53:26 FILE 'REGISTRY'  
FULL SCREEN SEARCH COMPLETED - 581 TO ITERATE

100.0% PROCESSED 581 ITERATIONS  
SEARCH TIME: 00.00.01

439 ANSWERS

L30 439 SEA SSS FUL L14 AND L13

=> \

L29 ANSWER 37 OF 37 CAPLUS COPYRIGHT 2003 ACS on STN  
 AN 2002:119352 CAPLUS  
 DN 136:175472  
 TI Positive photosensitive composition for photofabrication using deep UV ray  
 IN Kodama, Kunihiko; Aoai, Toshiaki  
 PA Fuji Photo Film Co., Ltd., Japan  
 SO Eur. Pat. Appl., 120 pp.  
 CODEN: EPXXDW

DT Patent

LA English

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 1179750	A1	20020213	EP 2001-117796	20010802
	R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO				
	JP 2002122994	A2	20020426	JP 2001-188670	20010621
	US 2002051933	A1	20020502	US 2001-921691	20010806
	US 6492091	B2	20021210		
PRAI	JP 2000-240059	A	20000808		

AB A pos. photosensitive compn. comprises: (A) a compd. generating an acid upon irradn. with one of an actinic ray and radiation; (B) a resin contg. a monocyclic or polycyclic alicyclic hydrocarbon structure and increasing the solv. to an alkali developer by the action of an acid; and (C) an onium salt of carboxylic acid. The present invention relates to a pos. photosensitive compn. for use in the prodn. process of a semiconductor such as IC, in the prodn. of a circuit board such as liq. crystal and thermal head, and in other photofabrication processes.

IT 398141-62-3 398141-63-4

RL: TEM (Technical or engineered material use); USES (Uses)  
 (onium salt; deep UV photofabrication pos. photoresist compn.  
 contg.)

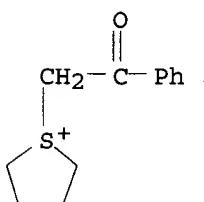
RN 398141-62-3 CAPLUS

CN Thiophenium, tetrahydro-1-(2-oxo-2-phenylethyl)-, methanesulfonate (9CI)  
 (CA INDEX NAME)

CM 1

CRN 58162-29-1

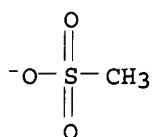
CMF C12 H15 O S

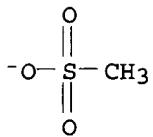


CM 2

CRN 16053-58-0

CMF C H3 O3 S

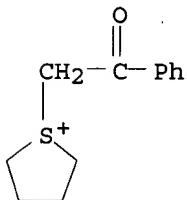




RN 398141-63-4 CAPLUS  
 CN Cholan-24-oic acid, 3,7,12-trihydroxy-, ion(1-),  
 (3.alpha.,5.beta.,7.alpha.,12.alpha.)-, tetrahydro-1-(2-oxo-2-  
 phenylethyl)thiophenium (9CI) (CA INDEX NAME)

CM 1

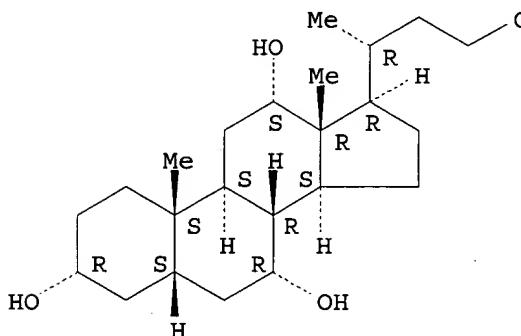
CRN 58162-29-1  
 CMF C12 H15 O S



CM 2

CRN 298-43-1  
 CMF C24 H39 O5

Absolute stereochemistry.



IT 301664-71-1 301664-72-2 398141-19-0  
 398141-23-6

RL: TEM (Technical or engineered material use); USES (Uses)  
 (photoacid generator; deep UV photofabrication pos. photoresist  
 compn. contg.)

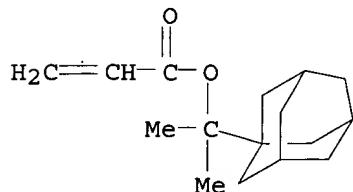
391613-77-7 CAPLUS

CN 2-Propenoic acid, 3-hydroxytricyclo[3.3.1.13,7]dec-1-yl ester, polymer with .alpha.,.alpha.-dimethylbicyclo[2.2.1]hept-5-ene-2-methanol, 2,5-furandione and 1-methyl-1-tricyclo[3.3.1.13,7]dec-1-yethyl 2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 300833-10-7

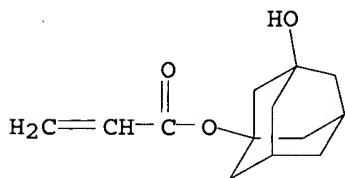
CMF C16 H24 O2



CM 2

CRN 216581-76-9

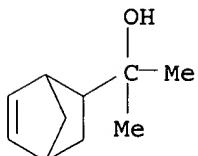
CMF C13 H18 O3



CM 3

CRN 22497-08-1

CMF C10 H16 O



L5 ANSWER 3 OF 30 CAPLUS COPYRIGHT 2002 ACS  
AN 2002:793943 CAPLUS  
DN 137:317924  
TI Perfluoroalkylsulfonic acid compounds for photoresists  
IN Ferreira, Lawrence; Blakeney, Andrew J.; Spaziano, Gregory Dominic; Dimov,  
Ognian; Kocab, Thomas J.; Hatfield, John P.  
PA Arch Specialty Chemicals, Inc., USA  
SO PCT Int. Appl., 81 pp.  
CODEN: PIXXD2

DT Patent

LA English

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	WO 2002082185	A1	20021017	WO 2002-US10800	20020405

W: JP, KR, SG

RW: AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL,  
PT, SE, TR

PRAI US 2001-281652P P 20010405

OS MARPAT 137:317924

AB The present invention relates to a photoacid compd. that produce a fluorinated alkyl sulfonic acid having a short perfluoroalkyl chain attached to an ether linkage. The invention photoacid has general structure: R-O(CF<sub>2</sub>)<sub>n</sub>SO<sub>3</sub>X (n = 1-4; R = C<sub>1</sub>-C<sub>12</sub> alkyl or alkenyl, aralkyl, aryl, bicycloalkyl, tricycloalkyl, H, alkyl sulfonic acid, perfluoroalkyl, general structure F((CF<sub>2</sub>)<sub>p</sub>O)<sub>m</sub>(CF<sub>2</sub>)<sub>q</sub>; p = 1-4; m = 0-3; q = 1-4; etc.; X = org. cations and covalently bonded org. radicals). The present invention relates **photoresist** compn comprising such photoacid generator compd.

IT 414911-37-8

RL: TEM (Technical or engineered material use); USES (Uses)  
(photoacid for photoresists compn. and photolithog.)

RN 414911-37-8 CAPLUS

CN Thiophenium, tetrahydro-1-(2-oxo-2-phenylethyl)-, salt with  
1,1,2,2-tetrafluoro-2-(pentafluoroethoxy)ethanesulfonic acid (1:1) (9CI)  
(CA INDEX NAME)

CM 1

CRN 220689-13-4

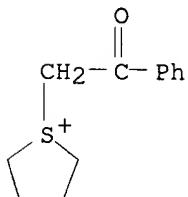
CMF C4 F9 O4 S

-O<sub>3</sub>S-CF<sub>2</sub>-CF<sub>2</sub>-O-CF<sub>2</sub>-CF<sub>3</sub>

CM 2

CRN 58162-29-1

CMF C12 H15 O S

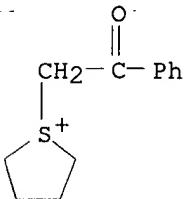


IT 58162-29-1

RL: TEM (Technical or engineered material use); USES (Uses)  
(sulfonium cation; prepn. of photoacid for photoresists compn. and  
photolithog.)

RN 58162-29-1 CAPLUS

CN Thiophenium, tetrahydro-1-(2-oxo-2-phenylethyl)- (9CI) (CA INDEX NAME)



RE.CNT 7 THERE ARE 7 CITED REFERENCES AVAILABLE FOR THIS RECORD  
ALL CITATIONS AVAILABLE IN THE RE FORMAT

L5 ANSWER 10 OF 30 CAPLUS COPYRIGHT 2002 ACS

AN 2002:707243 CAPLUS

DN 137:217798

TI Highly UV-sensitive radically polymerizable compositions without  
sensitizers

IN Uesugi, Takahiko; Arishima, Shinji; Yagi, Tamao

PA Toyo Ink Mfg. Co., Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 23 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2002265512	A2	20020918	JP 2001-67938	20010312
	WO 2002072640	A1	20020919	WO 2002-JP2303	20020312

W: CN, KR, US  
RW: AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL,  
PT, SE, TR

PRAI JP 2001-67938 A 20010312

OS MARPAT 137:217798

AB The compns., useful for moldings, coatings, photoresists, etc., contain initiators C6R5COCR3R4S+R1R2.Z- (R = H, alkyl, alkoxy, acyloxy, halo, NR5R6, .gtreq.1 of R are NR5R6, R1-R6 = H, alkyl, aryl; Z- = anion) and radically polymerizable compds. Thus, a cyclohexanone soln. of 100 parts pentaerythritol triacrylate and 6 parts p-Me2NC6H4COCH2S+Me2.BBuPh- manufd. from p-Me2NC6H4COCH2S+Me2.Br- and Li+BBuPh- was applied on a glass plate and dried to give a light yellow layer, which was irradiated with UV at 350-380 nm and '80 mJ/cm2 to give a colorless layer.

IT 457645-65-7P

RL: CAT (Catalyst use); IMF (Industrial manufacture); PREP (Preparation);  
USES (Uses)

(initiators for highly UV-sensitive radically polymerizable compns.  
without sensitizers)

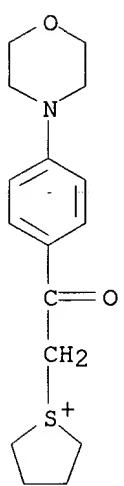
RN 457645-65-7 CAPLUS

CN Thiophenium, tetrahydro-1-[2-[4-(4-morpholinyl)phenyl]-2-oxoethyl]-,  
(T-4)-butyltriphenylborate(1-) (9CI) (CA INDEX NAME)

CM 1

CRN 457645-64-6

CMF C16 H22 N O2 S



L5 ANSWER 16 OF 30 CAPLUS COPYRIGHT 2002 ACS  
 AN 2002:314503 CAPLUS  
 DN 136:348304  
 TI Positive photosensitive composition  
 IN Kodama, Kunihiko; Aoai, Toshiaki  
 PA Fuji Photo Film Co., Ltd., Japan  
 SO Eur. Pat. Appl., 148 pp.  
 CODEN: EPXXDW

DT Patent

LA English

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 1199603	A1	20020424	EP 2001-124329	20011019
	R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR				
	JP 2002131897	A2	20020509	JP 2000-321128	20001020
	JP 2002214774	A2	20020731	JP 2001-132546	20010427
	US 2002102491	A1	20020801	US 2001-978103	20011017
PRAI	JP 2000-321128	A	20001020		
	JP 2000-352899	A	20001120		
	JP 2001-132546	A	20010427		

AB A pos. photosensitive compn. comprises a compd. capable of generating a specified sulfonic acid upon irradn. with one of an actinic ray and radiation and a resin capable of decompg. under the action of an acid to increase the solv. in an alkali developer.

IT 301664-71-1 398141-19-0 414911-37-8  
 414911-60-7 414911-65-2 414911-75-4  
 414911-76-5

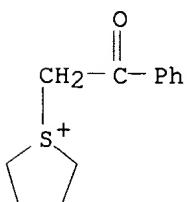
RL: TEM (Technical or engineered material use); USES (Uses)  
 (photo-acid generator used in pos. photoresist compn.)

RN 301664-71-1 CAPLUS

CN Thiopheniun, tetrahydro-1-(2-oxo-2-phenylethyl)-, salt with  
 1,1,2,2,3,3,4,4,4-nonafluoro-1-butanesulfonic acid (1:1) (9CI) (CA INDEX  
 NAME)

CM 1

CRN 58162-29-1  
 CMF C12 H15 O S



CM 2

CRN 45187-15-3  
 CMF C4 F9 O3 S

-O3S- (CF2)3 - CF3

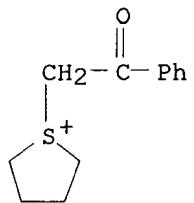
RN 398141-19-0 CAPLUS

CN Thiophenium, tetrahydro-1-(2-oxo-2-phenylethyl)-, salt with  
trifluoromethanesulfonic acid (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 58162-29-1

CMF C12 H15 O S



L5 ANSWER 18 OF 30 CAPLUS COPYRIGHT 2002 ACS  
AN 2000:739615 CAPLUS

DN 133:315619

TI Positive-working **resist composition**

IN Fujimura, Satoshi; Katashima, Miwa; Haneda, Hideo; Iwai, Takeshi

PA Tokyo Ohka Kogyo Co., Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 9 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2000292917	A2	20001020	JP 1999-98796	19990406

OS MARPAT 133:315619

AB In the title resist compn. contg. (1) a polymer in which the H atoms of the carboxyl groups are substituted by an acid-dissocg. group having alkali dissoln.-inhibiting ability and the acid-dissocg. group is dissocd. by the action of the acid generated by exposure to increase the solv. to aq. alkali solns. and (2) a compd. generating an acid by irradn. with radiation, the acid generator is a mixt. of (a) a triphenylsulfonium salt having substituted or unsubstituted benzene nuclei and (b) a sulfonium salt I (Ar = aryl; X- = Cl-15 fluoroalkylsulfonic acid ion) in a (a)/(b) ratio of 5-25 wt.%. The compn. shows high photosensitivity and provides high resoln. patterns with good profile by using ArF excimer lasers.

IT 301664-71-1 301664-72-2

RL: TEM (Technical or engineered material use); USES (Uses)  
(pos. resist compn. contg. polymer having acid decomposable group and sulfonium compds. acid generators)

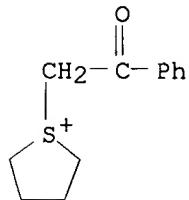
RN 301664-71-1 CAPLUS

CN Thiophenium, tetrahydro-1-(2-oxo-2-phenylethyl)-, salt with 1,1,2,2,3,3,4,4,4-nonafluoro-1-butanesulfonic acid (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 58162-29-1

CMF C12 H15 O S



CM 2

CRN 45187-15-3

CMF C4 F9 O3 S

-O3S- (CF2)3 - CF3

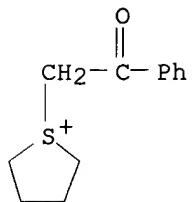
RN 301664-72-2 CAPLUS

CN Thiophenium, tetrahydro-1-(2-oxo-2-phenylethyl)-, salt with

1,1,2,2,3,3,4,4,5,5,6,6,7,7,8,8,8-heptadecafluoro-1-octanesulfonic acid  
(1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 58162-29-1  
CMF C12 H15 O S



CM 2

CRN 45298-90-6  
CMF C8 F17 O3 S

-O3S- (CF2)7 - CF3

L5 ANSWER 22 OF 30 CAPLUS COPYRIGHT 2002 ACS  
AN 1997:467621 CAPLUS  
DN 127:109943  
TI Light-sensitive polycyanurate compositions as photoresists and their preparation  
IN Hedrick, Jeffrey Curtis; Papathomas, Konstantinos I.; Tisdale, Stephen L.; Viehbeck, Alfred; Gelorme, Jeffrey Donald; Markovich, Voya Rista; Lewis, Thomas H.; Furniss, Stephen Joseph  
PA International Business Machines Corporation, USA  
SO Jpn. Kokai Tokyo Koho, 16 pp.  
CODEN: JKXXAF

DT Patent  
LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 09137059	A2	19970527	JP 1996-242987	19960913
	JP 3177173	B2	20010618		
	US 5919596	A	19990706	US 1997-798592	19970211
PRAI	US 1995-528291	A	19950914		

AB The curable crack-resistant compns., useful for circuit boards and electronic packaging, contain (1) thermosetting materials comprising cyanate resins and/or their prepolymers, (2) reactive halogen-contg. thermoplastic resins as modifiers, and (3) photosensitizers. Preferably, component 2 is a F-contg. polyoxyarylene and component 3 contains a cation of a Group IV-VIII transition metal.

IT 58162-30-4 71967-58-3 191981-90-5

RL: CAT (Catalyst use); USES (Uses)  
(photosensitizers; light-sensitive polycyanurate compns. as photoresists)

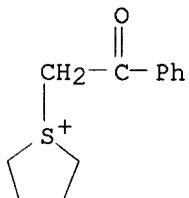
RN 58162-30-4 CAPLUS

CN Thiophenium, tetrahydro-1-(2-oxo-2-phenylethyl)-, hexafluoroarsenate(1-)  
(9CI) (CA INDEX NAME)

CM 1

CRN 58162-29-1

CMF C12 H15 O S

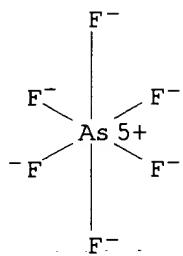


CM 2

CRN 16973-45-8

CMF As F6

CCI CCS



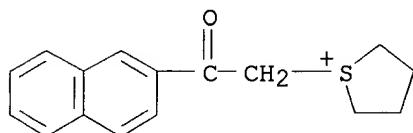
RN 71967-58-3 CAPLUS

CN Thiophenium, tetrahydro-1-[2-(2-naphthalenyl)-2-oxoethyl]-, tetrafluoroborate(1-) (9CI) (CA INDEX NAME)

CM 1

CRN 71967-57-2

CMF C16 H17 O S

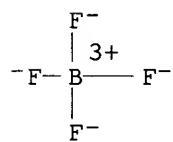


CM 2

CRN 14874-70-5

CMF B F4

CCI CCS



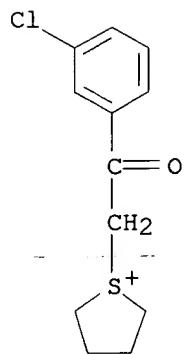
RN 191981-90-5 CAPLUS

CN Thiophenium, 1-[2-(3-chlorophenyl)-2-oxoethyl]tetrahydro-, hexafluoroarsenate(1-) (9CI) (CA INDEX NAME)

CM 1

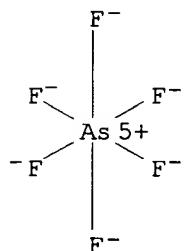
CRN 137309-31-0

CMF C12 H14 Cl O S



CM 2

CRN 16973-45-8  
CMF As F6  
CCI CCS



L5 ANSWER 23 OF 30 CAPLUS COPYRIGHT 2002 ACS  
AN 1997:9 CAPLUS  
DN 126:39711  
TI Visible-light polymerization initiator and visible-light polymerizable composition  
IN Kazama, Hideki; Satoh, Takeshi; Oguri, Makoto  
PA Tokuyama Corporation, Japan  
SO Eur. Pat. Appl., 39 pp.  
CODEN: EPXXDW  
DT Patent  
LA English

(FILE 'HOME' ENTERED AT 15:06:55 ON 03 DEC 2002)

FILE 'REGISTRY' ENTERED AT 15:07:06 ON 03 DEC 2002

L1                   STRUCTURE UPLOADED

L2                   106 S L1 FULL

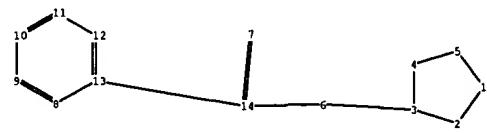
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L3                   96 S L2

L4                   30380 S PHOTORESIST OR RESIST COMPOSITION

L5                   30 S L3 AND L4

=> d 12



chain nodes :

6 7 14

ring nodes :

1 2 3 4 5 8 9 10 11 12 13

chain bonds :

3-6 6-14 7-14 13-14

ring bonds :

1-2 1-5 2-3 3-4 4-5 8-9 8-13 9-10 10-11 11-12 12-13

exact/norm bonds :

7-14

exact bonds :

1-2 1-5 2-3 3-4 3-6 4-5 6-14 13-14

normalized bonds :

8-9 8-13 9-10 10-11 11-12 12-13

Match level :

1:Atom 2:Atom 3:Atom 4:Atom 5:Atom 6:CLASS 7:CLASS 8:Atom 9:Atom  
10:Atom 11:Atom 12:Atom 13:Atom 14:CLASS

L5 ANSWER 18 OF 30 CAPLUS COPYRIGHT 2002 ACS  
AN 2000:739615 CAPLUS  
DN 133:315619

TI Positive-working **resist composition**

IN Fujimura, Satoshi; Katahima, Miwa; Haneda, Hideo; Iwai, Takeshi

PA Tokyo Ohka Kogyo Co., Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 9 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

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OS	MARPAT 133:315619				

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IT 301664-71-1 301664-72-2

RL: TEM (Technical or engineered material use); USES (Uses)  
(pos. resist compn. contg. polymer having acid decomposable group and sulfonium compds. acid generators)

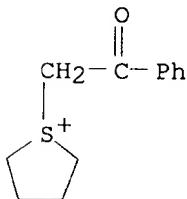
RN 301664-71-1 CAPLUS

CN Thiophenium, tetrahydro-1-(2-oxo-2-phenylethyl)-, salt with 1,1,2,2,3,3,4,4,4-nonafluoro-1-butanesulfonic acid (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 58162-29-1

CMF C12 H15 O S



CM 2

CRN 45187-15-3

CMF C4 F9 O3 S

-O3S- (CF2)3-CF3

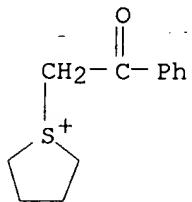
RN 301664-72-2 CAPLUS

CN Thiophenium, tetrahydro-1-(2-oxo-2-phenylethyl)-, salt with

1,1,2,2,3,3,4,4,5,5,6,6,7,7,8,8,8-heptadecafluoro-1-octanesulfonic acid  
(1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 58162-29-1  
CMF C12 H15 O S



CM 2

CRN 45298-90-6  
CMF C8 F17 O3 S

$-\text{O}_3\text{S}- (\text{CF}_2)_7-\text{CF}_3$